

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of)
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Byeung-leul LEE et al.) Group Art Unit: Unassigned
)
Application No.: New Application) Examiner: Unassigned
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Filed: Herewith)
)
For: METHOD OF REDUCING)
NOTCHING DURING REACTIVE)
ION ETCHING)

PRELIMINARY AMENDMENT

Assistant Commissioner for Patents
Washington, D.C. 20231

Sir:

Prior to examination on the merits, kindly amend the above-captioned application as follows:

IN THE SPECIFICATION:

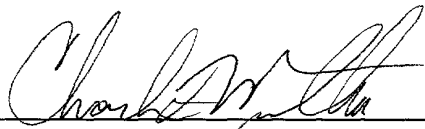
Kindly add the following paragraph on page 1, after the title of the invention and before the "Background of the Invention," --Priority is claimed to Patent Application Number 2001-12629, filed in the Republic of Korea on March 12, 2001, herein incorporated by reference.--

REMARKS

A change has been made to the specification by the above amendments. Favorable action on the merits is respectfully requested.

Respectfully submitted,

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